OUPONT

DuPont[™] CuSolve[™] EKC[™]575

Post Etch Residue Remover

Introduction

DuPont[™] EKC[™]575 post etch residue remover is an aqueous cleaning solution designed specifically to address TiN metal hard mask pullback *in situ* during cleaning. The product is provided as a concentrate which is activated by the addition of hydrogen peroxide at point of use. Peroxide concentration, process temperature, and process time enable a controlled, selective and tunable removal of TiN metal hard mask *in situ* during the clean process. The product is qualified for 28 nm Cu Dual-Damascene application.

Cleaning Performance

- Complete removal of etch polymer residues
- Complete removal of Ti(x)F(y) residues and Cu oxides
- Compatible with low-k (such as SiOC, k=2.5) and Cu

TiN and Cu Etch Rate vs. H₂O₂ and Temperature

- TiN etch rate increases with $\rm H_2O_2$ concentration and process temperature
- Cu etch rate increases with H₂O₂ concentration
- The TiN etch rate can be tuned by varying H₂O₂ concentration and process temperatures according to customer requirements

Figure 1. Contour Plot of TiN and Cu Etch Rates



Table 1. Etch Rates for Various Materials

EKC [∞] 575 + 20% H ₂ O ₂ (30%) at 30 °C					
Cu (Å/min)	TiN (Å/min)	TEOS (Å/min	BD2 (Å/min)		
<2	30 ±2	0.5 ±0.3	0.5 ±0.3		

Figure 2. Illustrations of TiN Removal and Cleaning Performance



Pre-Clean





Post Clean EKC[™]575–TiN Pull Back





Post Clean EKC[™]575–TiN Removed



Single Wafer Process Recommendation

- Mix EKC[™]575 with 30% hydrogen peroxide (4:1) prior to use (e.g., 7.5 L of 30% peroxide added to 30 L of EKC[™]575 for a 40 L tank)
- Mix by recirculation through the tool for 20–30 min
- Set process temperature to 25 to 45 °C (optimum 30 °C)
- Process time: 120 sec (range is 60 to 150 sec)
- Flow rate: 1–2 L/min
- TiN: Cu selectivity is governed by pH, peroxide concentration and temperature
- Process time can be readily adjusted to control the level of TiN removal partial recess
- 30% hydrogen peroxide semiconductor grade is recommended

Material Compatibility

EKC[™]575 (activated with peroxide) and EKC[™]575 have been tested at 30 °C and are compatible with PFA, PP, HDPE, PVC, PTFE, PVDF, Kalrez[®] O-ring, and SS316.

Table 2. Physical and Chemical Properties

Parameter	EKC [™] 575 No Peroxide		EKC [™] 575 With Peroxide
pH	9.6–10		8.8–9.2
Flash Point (°C)	NA		NA
Surface Tension (dynes/cm, 24 °C)	65.1		NA
Freezing Point (°C)	-11.5		NA
Density (g/mL)	1.0014 (20 °C)	0.9982 (30 °C)	NA
Absolute Viscosity (cp)	1.10 (20 °C)	0.87 (30 °C)	NA
Kinematic Viscosity (cSt)	1.09 (20 °C)	0.88 (30 °C)	NA

Bathlife and Shelf life

- Typical bathlife is 12 hr when peroxide is added
- Shelf life is one year from date of manufacture

Safety

EKC[™]575 is a clear liquid with no odor and is non corrosive. Exposure to the eyes causes irritation, and exposure to the skin and respiratory tract may cause irritation. For further information please refer to the MSDS.

< DUPONT >

ekctech.dupont.com

For more information on DuPont[™] CuSolve[™] EKC[™]575 or other DuPont products, please visit our website.

The information provided in this data sheet corresponds to our knowledge on the subject at the date of its publication. It may be subject to revision as new knowledge and experience becomes available. This information is not intended to substitute for any testing you may need to conduct to determine for yourself the suitability of our products for your particular purposes. Since we cannot anticipate all variations in end-use and disposal conditions, DuPont makes no warranties and assumes no liability in connection with any use of this information. It is intended for use by persons having technical skill, at their own discretion and risk. Nothing in this publication is to be considered as a license to operate under or a recommendation to infringe any patent right.

CAUTION: Do not use in medical applications involving permanent implantation in the human body. For other medical applications, see "DuPont Medical Caution Statement,"H-50102-5 and "DuPont Policy Regarding Medical Applications"H-50103-5.

DuPont", the DuPont Oval Logo, and all products, unless otherwise noted, denoted with TM, SM or ® are trademarks, service marks or registered trademarks of affiliates of DuPont de Nemours, Inc. © 2019 DuPont de Nemours, Inc. All rights reserved.

K-25752-2 (06/19)